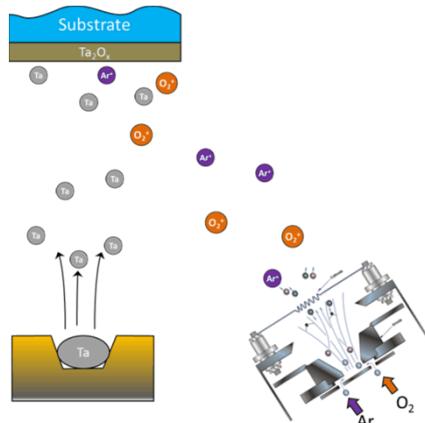


Tantalum Oxide Resistive Memory Devices by IAD

EM-WeM-1, Wednesday 8:00AM

Ronald S. Goeke¹, M.J. Marinella², D.R. Hughart², and S.A. Decker²

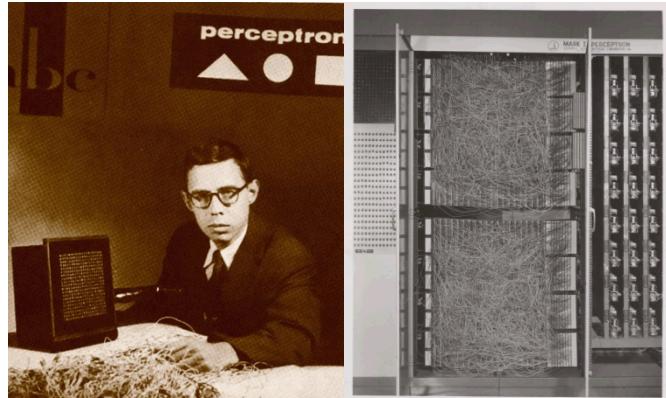
*Materials Science and Engineering Center¹
Microsystems Science and Technology Center²
Sandia National Laboratories, Albuquerque, NM, USA*



Neural-inspired Computing Hardware

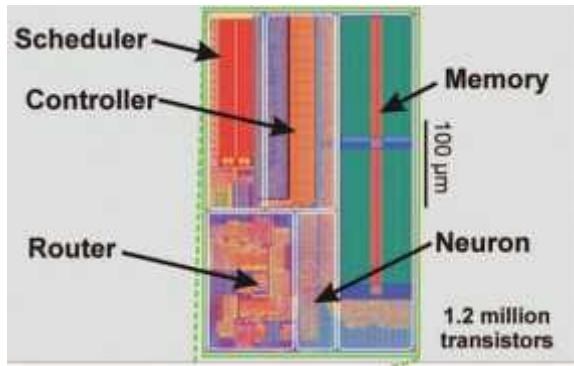
Revival of an Old Idea

Mark I Perceptron (Rosenblatt 1960):



Arvin Calspan Advanced Technology Center; Hecht-Nielsen, R. *Neurocomputing* (Reading, Mass.: Addison-Wesley, 1990); Cornell Library

DARPA , IBM TrueNorth (2014):



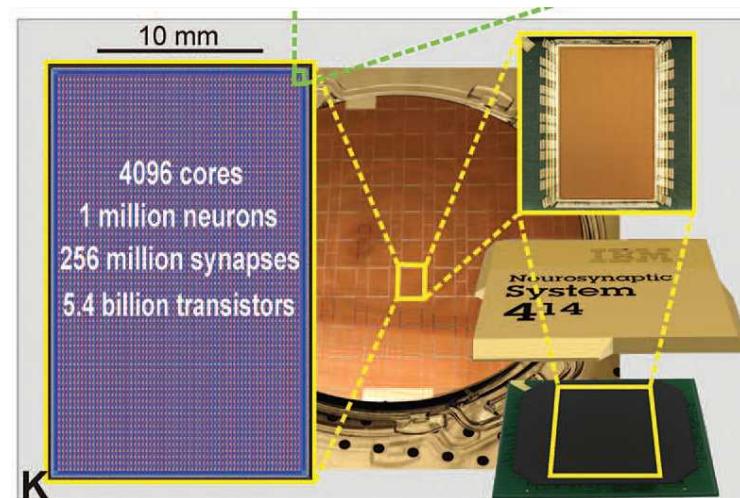
EU HBP, SpiNNaker (2014):



Neural Algorithm Computing

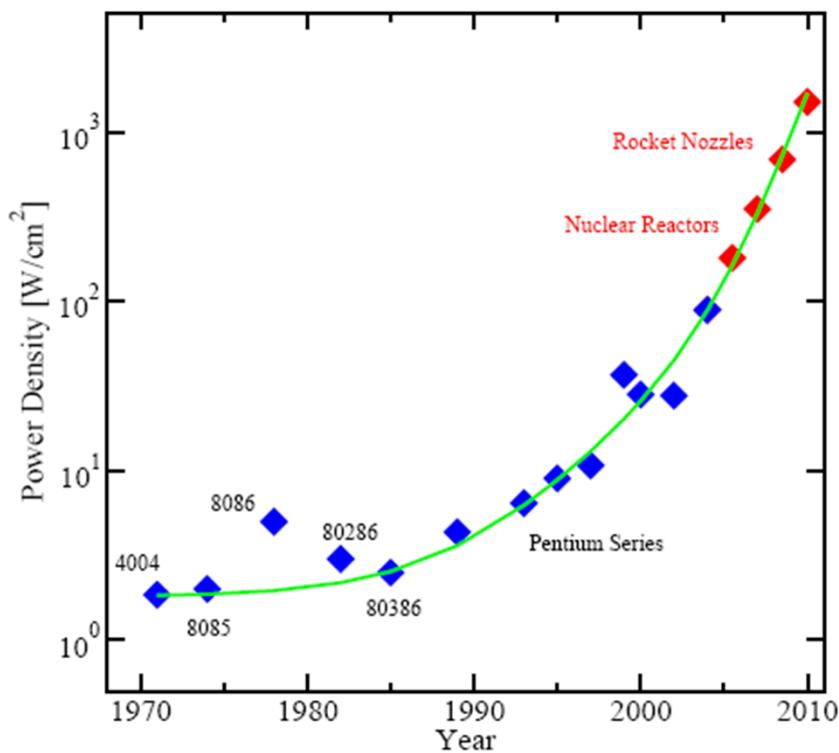
Current State of the Art

- **CPU/GPU**
 - Most general; common programming languages
 - Lowest power efficiency and performance
 - Memory separate from chip
 - Example: Google deep learning study (CPU→GPU)
- **FPGA**
 - General; requires hardware design language
 - Moderate performance and efficiency
- **Custom IC (Truenorth, Spinnaker)**
 - Specific: ex. executes STDP
 - Highest performance and efficiency
 - Expensive, 40MB local memory
 - Example: IBM Truenorth
- **Power ends up as a limiting factor**

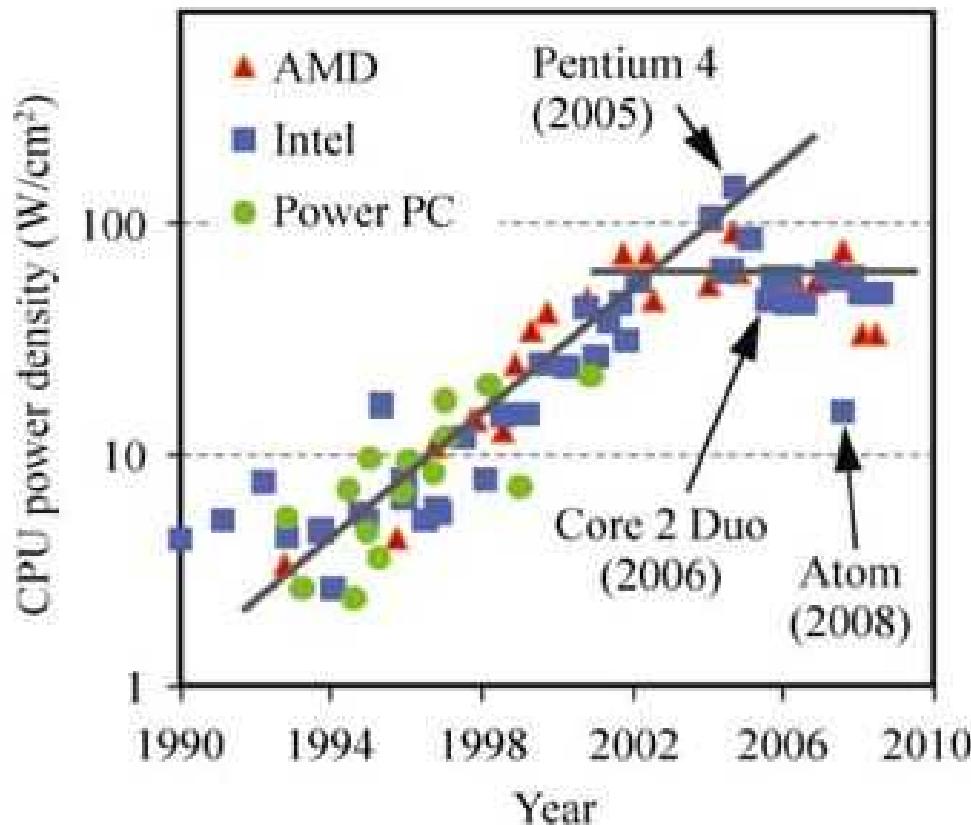


Heating During Computing is Enormous

Low power RAM needed



(a) Power loss density per die



<http://www.iue.tuwien.ac.at/phd/holzer/node11.html>

<http://www.nanotechnologies.qc.ca/blog/industry/energy-dissipation-nanoscale-devices>

Power Consumption is Also Enormous



Possible solution?

New devices and new computing paradigms will be needed in the near future.



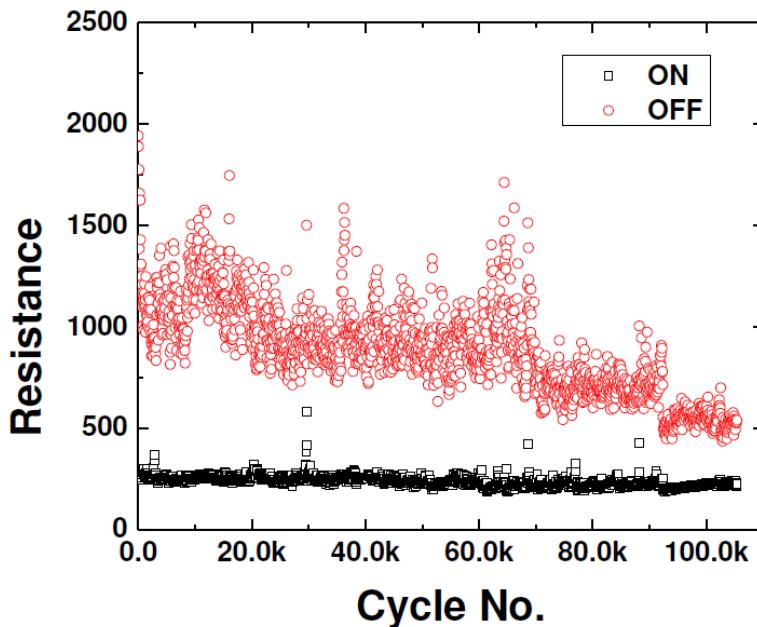
- Tianhe-2 - World's Fastest Supercomputer
- $\sim 3.4 \times 10^{16}$ flops/s, **~20 MW, room-sized**
- Nuclear reactors will soon be needed for every supercomputer.
- The Human Brain
- **20W, 1200 cm³**
- $\sim 10^{18}$ flops/s are believed to be needed for the human brain project.

Can Memristors Help?

ReRAM

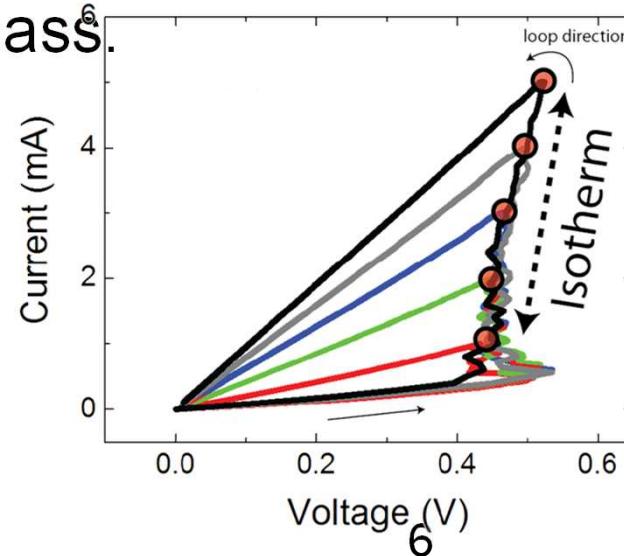
Resistive Memory

- A voltage or current can change the resistance to a 1 or a 0.



Novel Circuit Element

- Using partial voltages causes only partial changes.
- Similarly to synapses - as current passes, it becomes easier for more current to pass.



Why Do We Need an HW Accelerator?

Significant power savings

Problem: perceptron network training slow and extremely computationally intensive

Use simulation results for similar algorithm as example

Significant power savings using a memristor-based HW accelerator :

16x reduction in power over SRAM ASIC

6x reduction in chip area over SRAM ASIC

Equivalent to 6x improvement in performance/area

Configuration	# of chips	Chip area (mm ²)			Power (W)	Power eff. over Xeon
		% active				
Memristor Analog (config 4)	1	5.9	38.6%		0.07	234,859
Memristor Digital (config 5)	1	18.2	89.6%		0.62	16,968
SRAM (config 6)	1	29.1	89.6%		1.13	8,215
NVIDIA M2070	12	529.0	99.2%	2700.00		6
Intel Xeon X5650	179	240.0	99.9%	17005.00		1

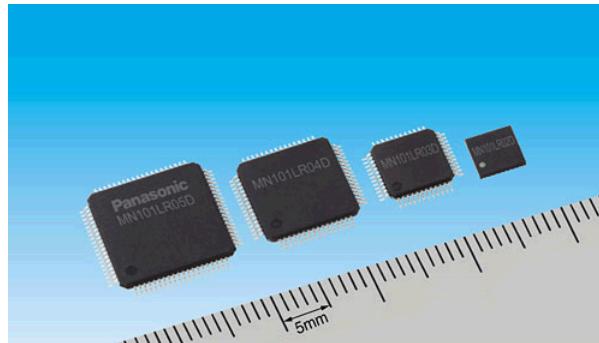
Memristors

Who's interested

Resistive Memory

- Panasonic recently released the first product.

Panasonic
ideas for life

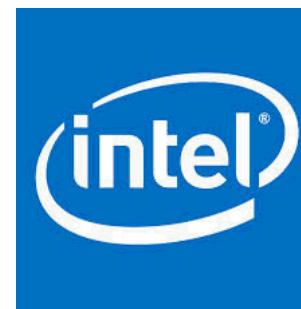
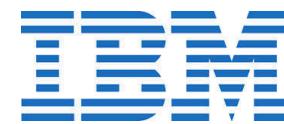


ReRAM Mounted Low Power Consumption Microcomputer, MN101LR Series

- They claim it is 5-10 times faster using half the power.
 - Probably saved in the wires.

Novel Circuit Element

- Brain-inspired computing using memristors is receiving heavy investment from big companies.



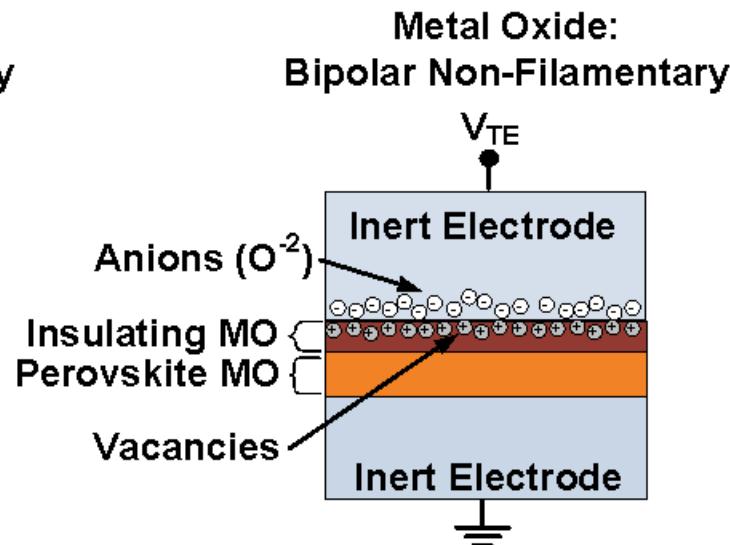
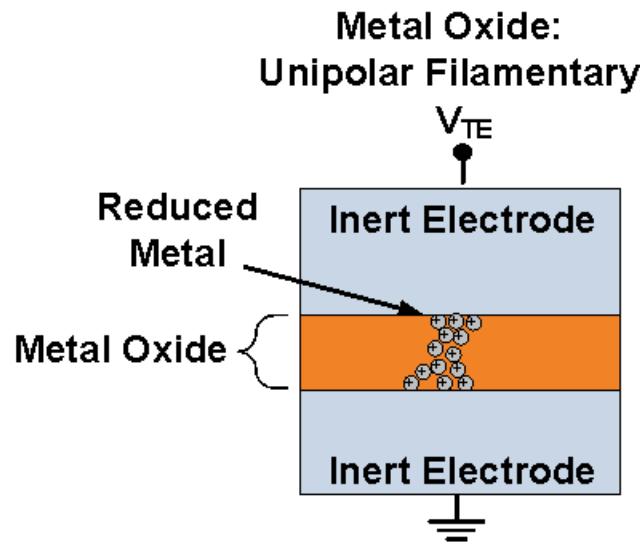
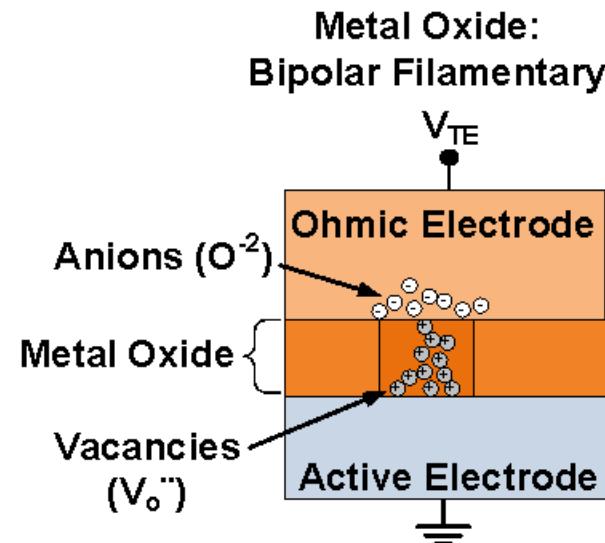
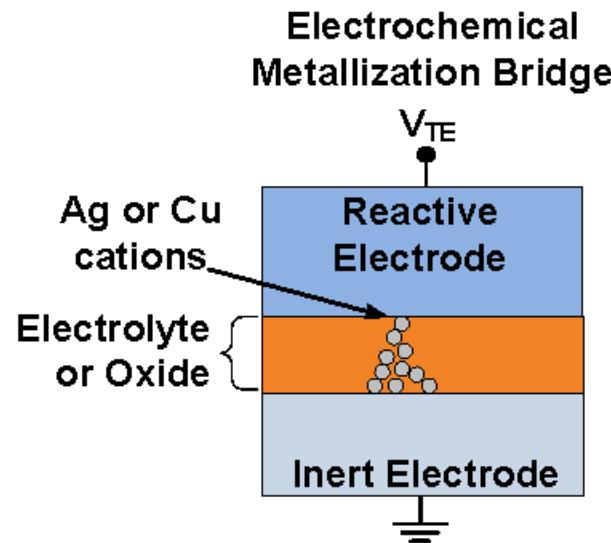
Brain Inspired Computing at Sandia

HAANA

- Sandia established a multidisciplinary LDRD project in neuromorphic computing project in October 2015
 - Hardware Acceleration of Adaptive Neural Algorithms (HAANA)
 - Algorithms research
 - Hardware and Device Architectures
 - Resistive Memory Devices
- Some of the initial work on development of resistive devices covered in this talk

Resistive Random Access Memory

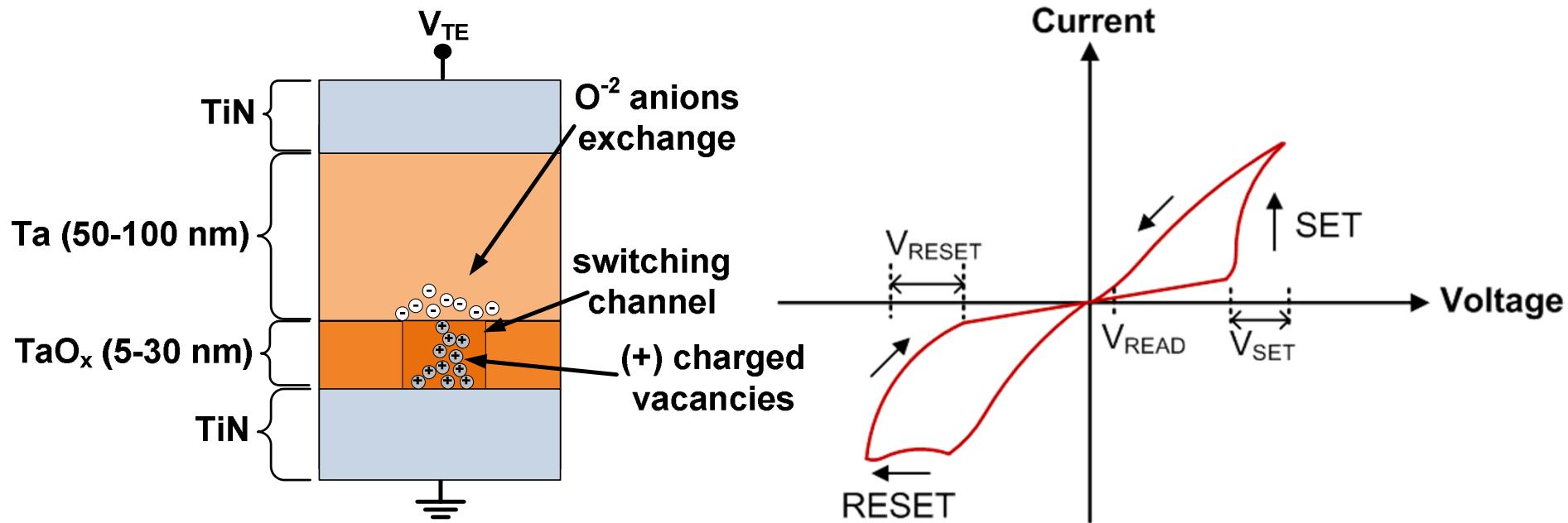
ReRAM



Valence Change ReRAM

TaO_x

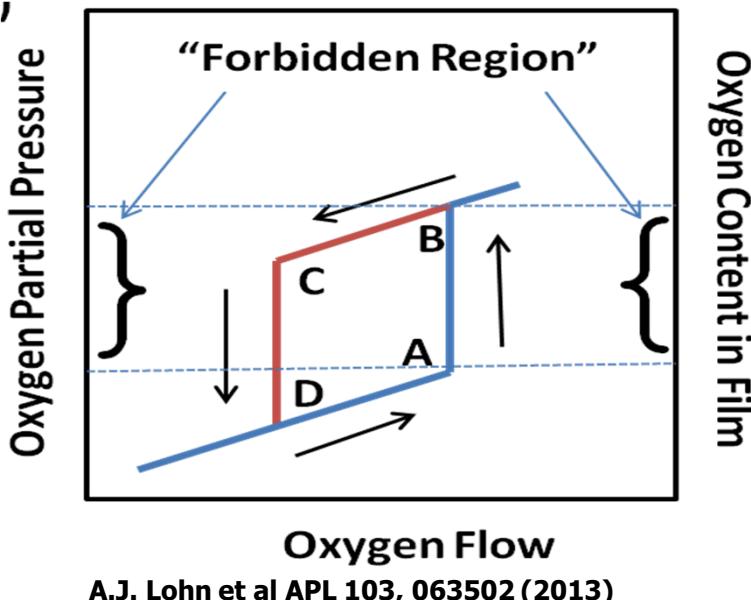
- “Hysteresis loop” is simple method to visualize operation
 - (real operation through positive and negative pulses)
- Resistance Change Effect (polarities depend on device):
 - Positive voltage/electric field: low R – O⁻² anions leave oxide
 - Negative voltage/electric field: high R – O⁻² anions return
- Common switching materials: TaO_x, HfO_x, TiO₂, ZnO



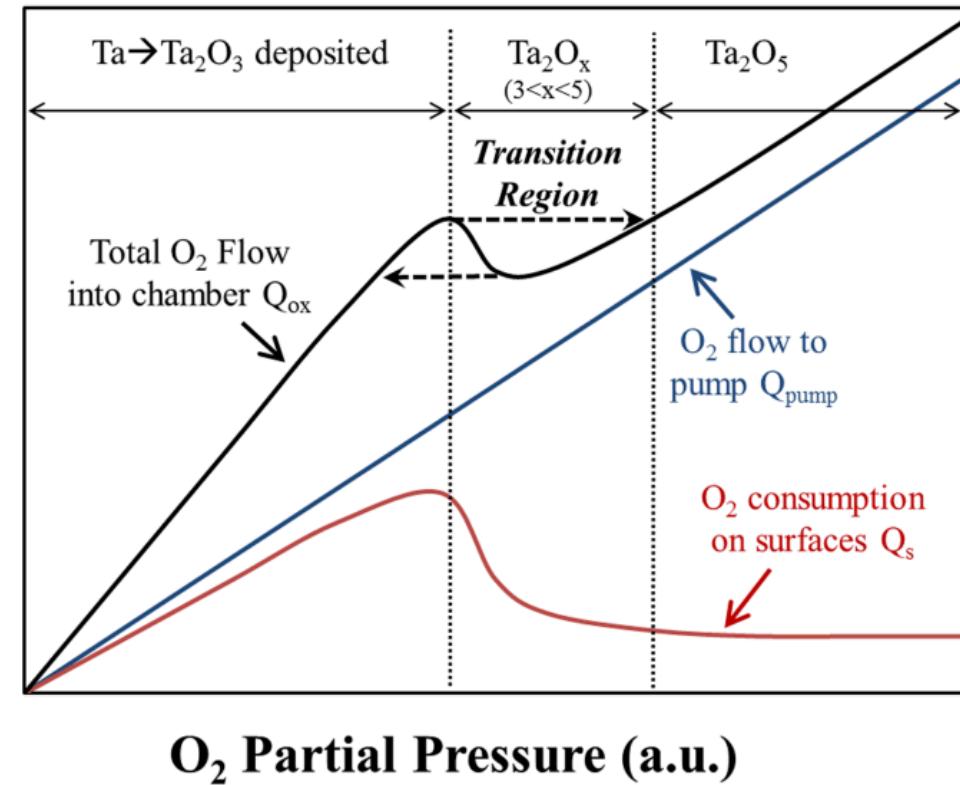
Switching Film Development:

Reactive Sputtering “Forbidden Region”

- One of the parameters that we vary is oxygen content
- **Forbidden oxygen flow-pressure region occurs due to target poisoning**
 - This is the region we need to be in to get ideal ReRAM stoichiometry



A.J. Lohn et al APL 103, 063502 (2013)



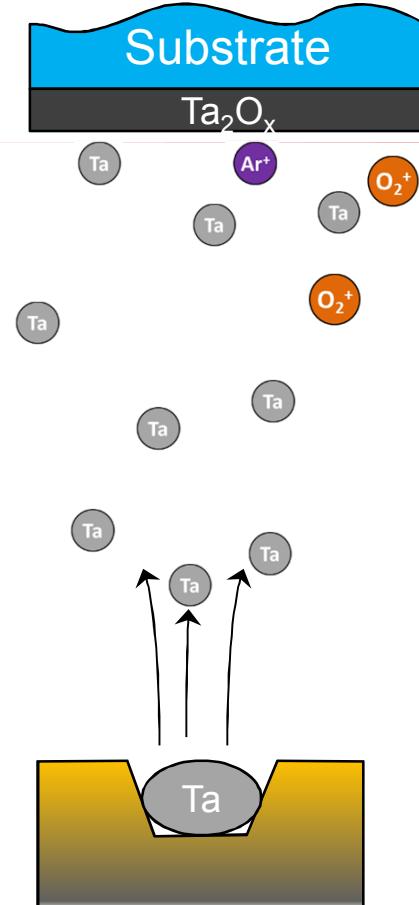
J.E. Stevens et al, J. Vac. Sci. Technol. A 32, 021501 (2014)

Ion Assisted Deposition (IAD)

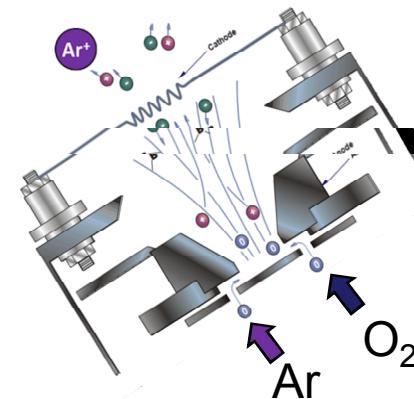
Stoichiometry control

Metal Evaporation
Rate Control

QCM



Oxidation control
Ion Beam Current
Gas flow rate
% O_2 in Ar/O_2 gas mixture

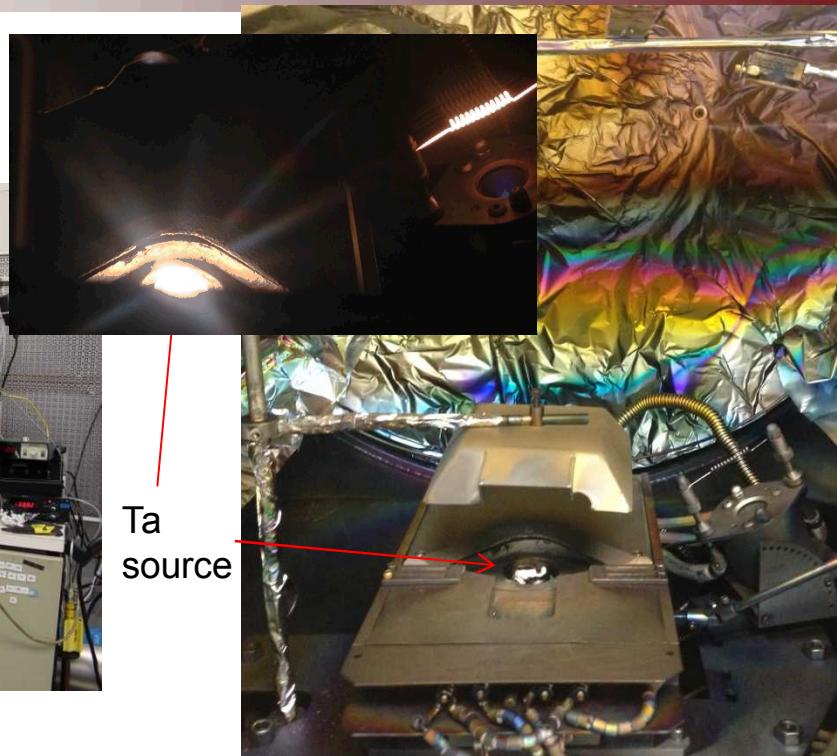
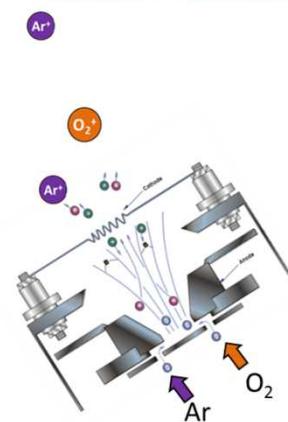
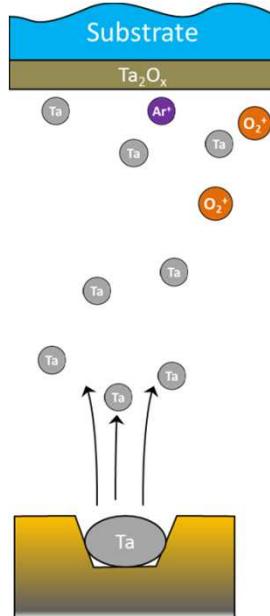


Ion Assisted Deposition (IAD)

System used for Ta_2O_x deposition

0.5 Å/s growth rate

33cm source to substrate



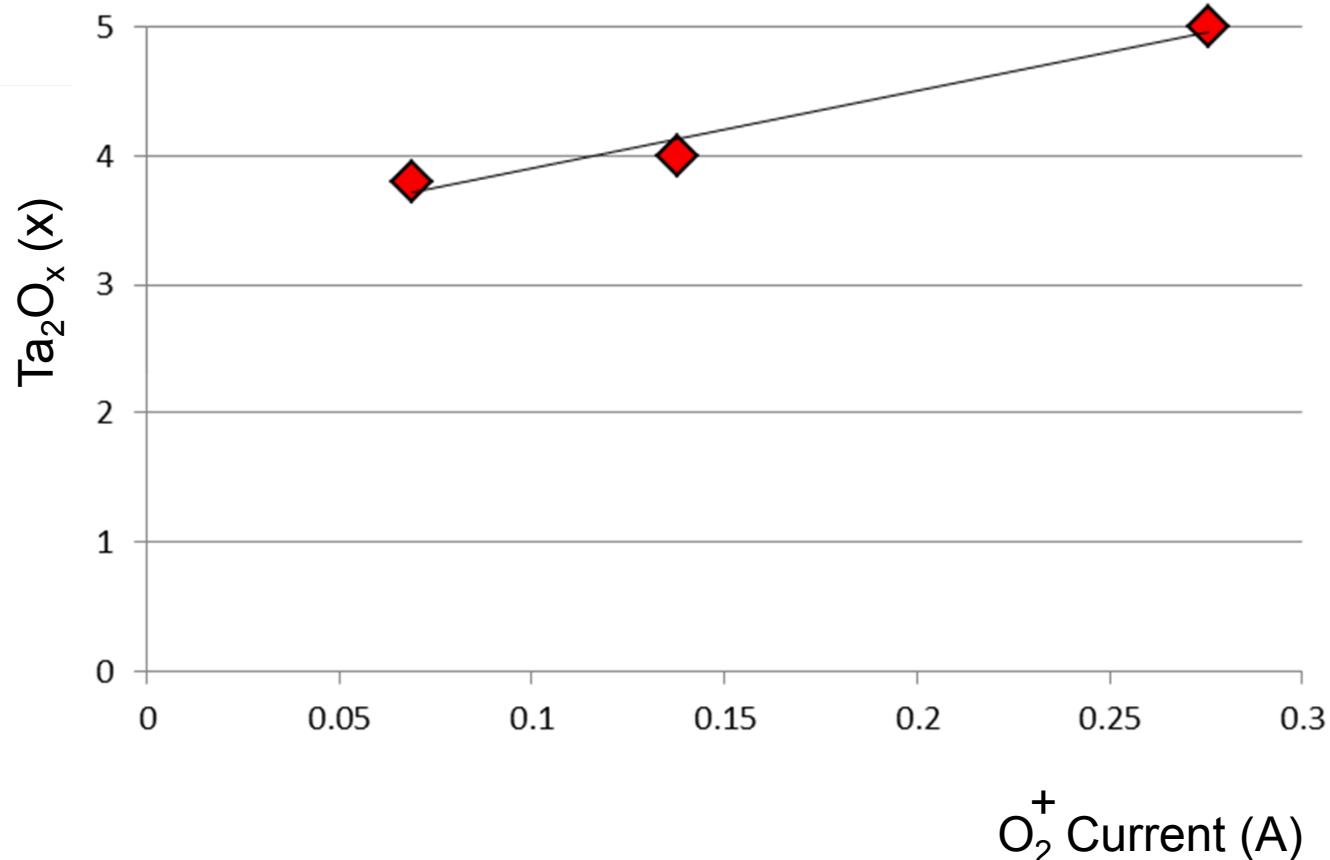
*Four pocket rotary turret
10kV electron beam gun,
and molten material during
deposition*

KRI EH200 ion gun
Gas mixture of Ar & O₂ @ 18 sccm



Stoichiometry Control

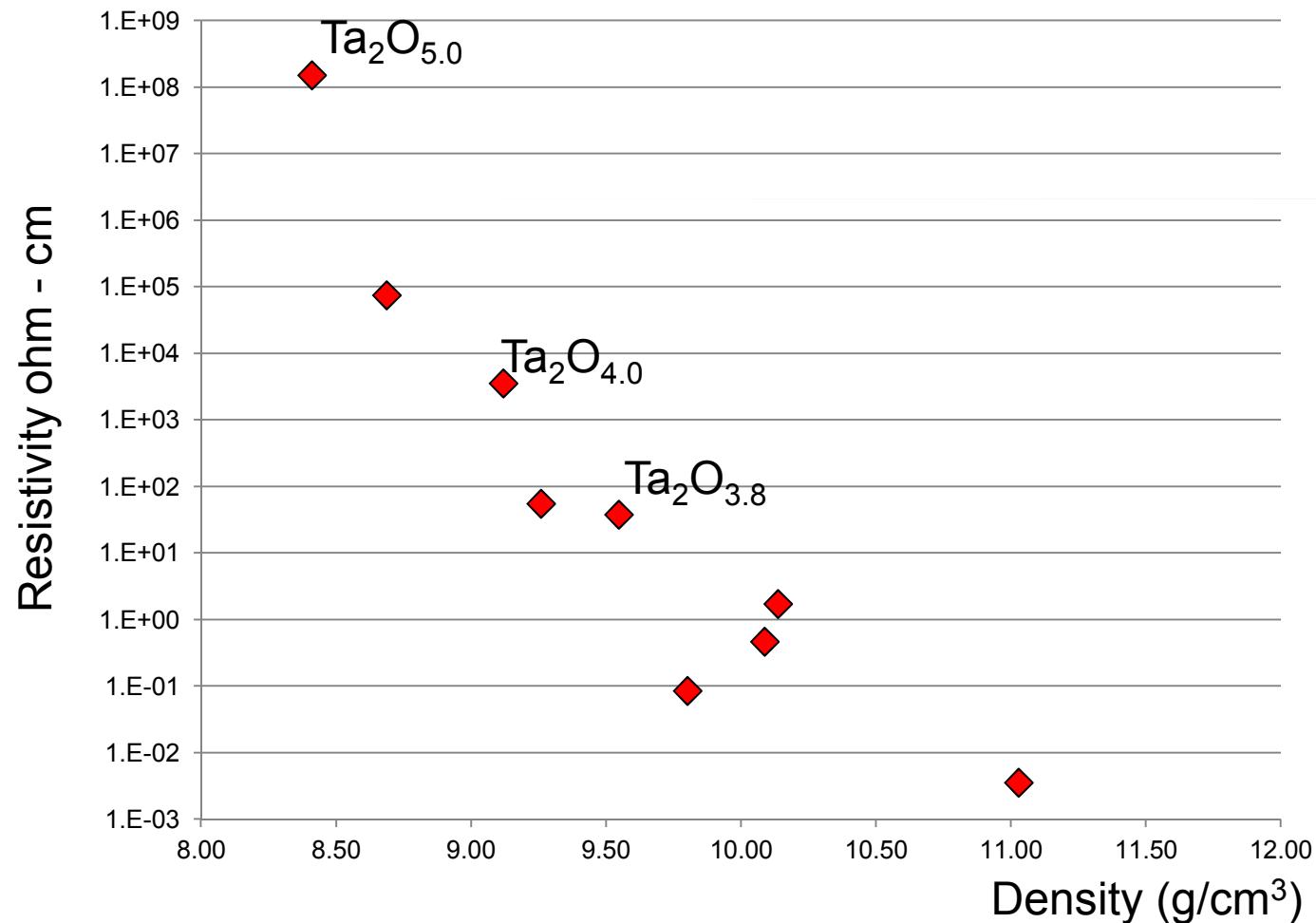
Ions and O₂ partial pressure



Ions contribute to system pressure and also react with growing film

IAD Film Resistivity

Density, resistivity and stoichiometry correlated

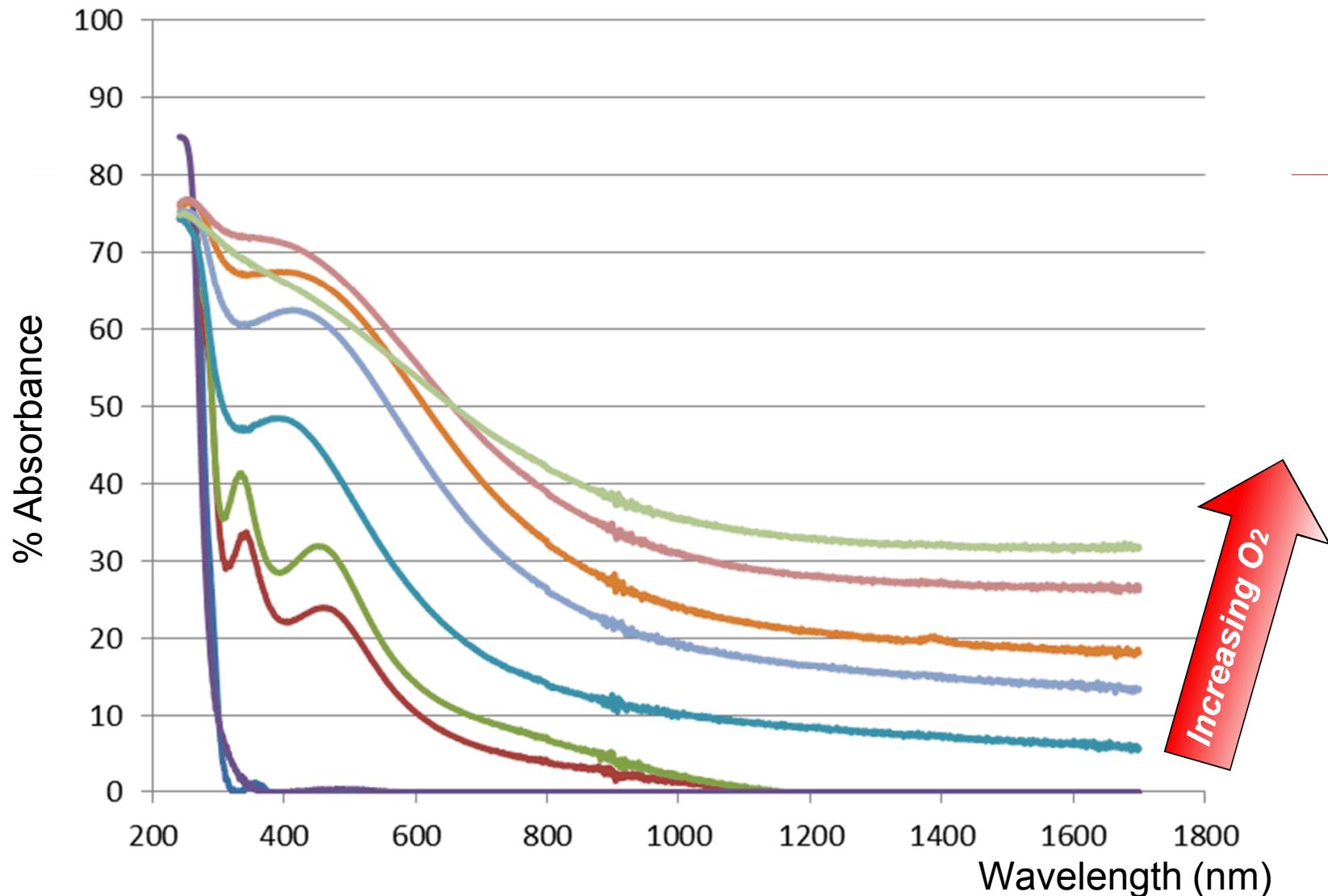


$$\text{Ta}_2\text{O}_5 = 8.37 \text{ g/cm}^3$$

$$\text{Ta} = 16.69 \text{ g/cm}^3$$

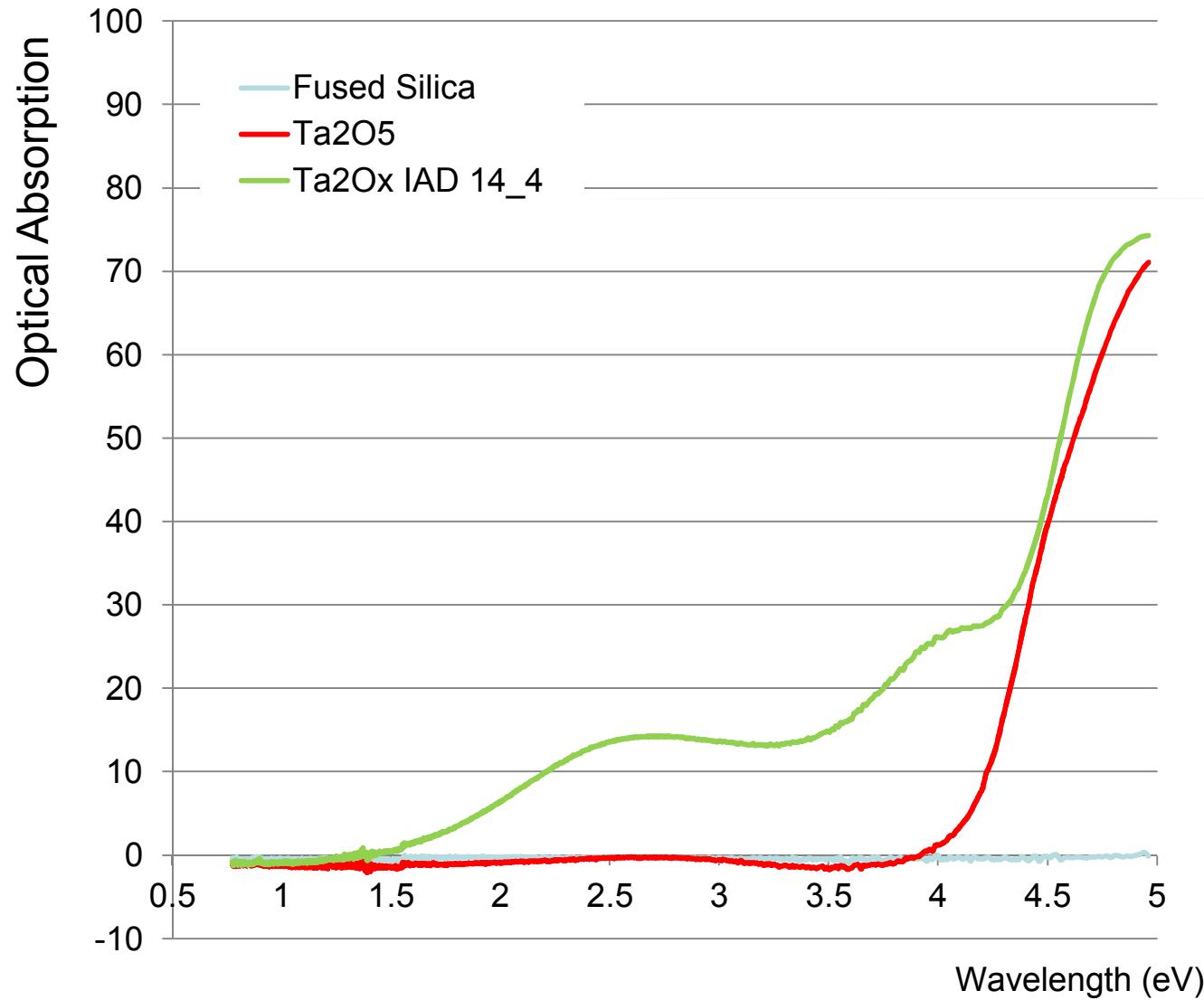
Optical Absorption

Spectrophotometry and Ellipsometry



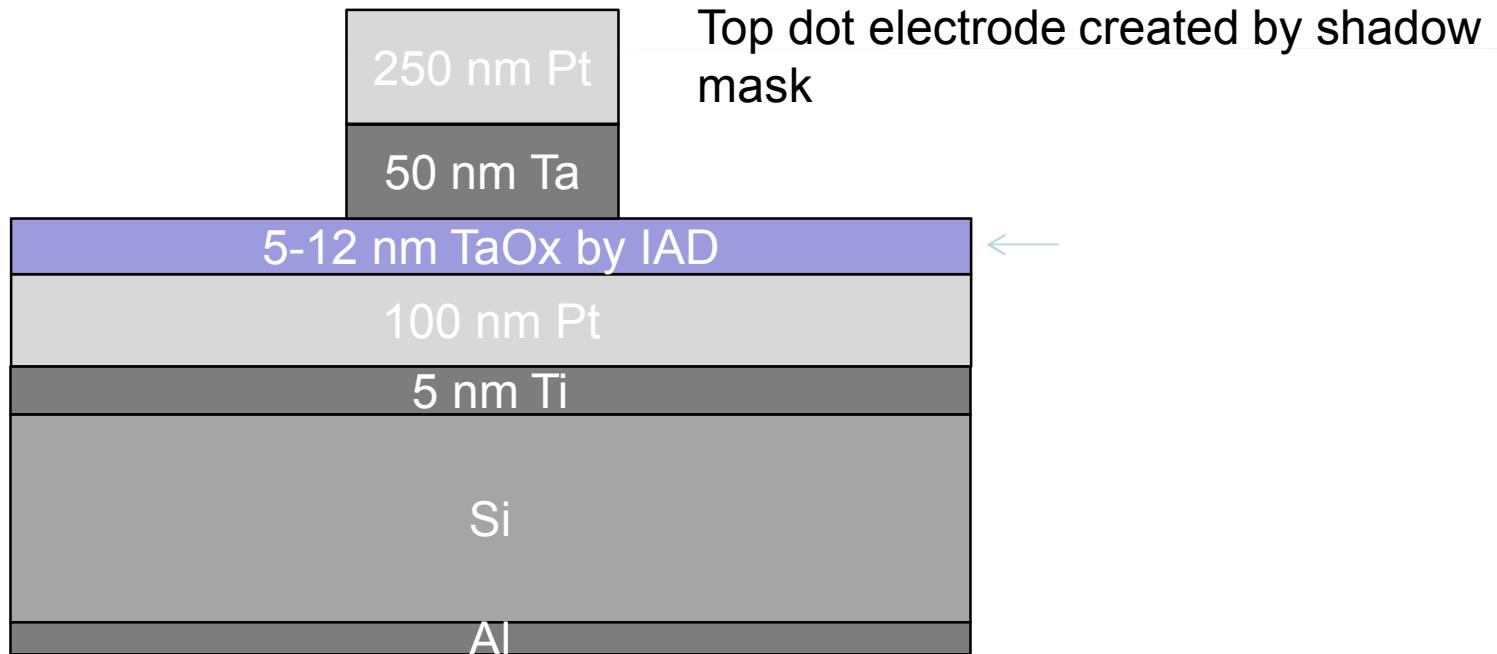
Band Gap Shift

Optical Absorbance



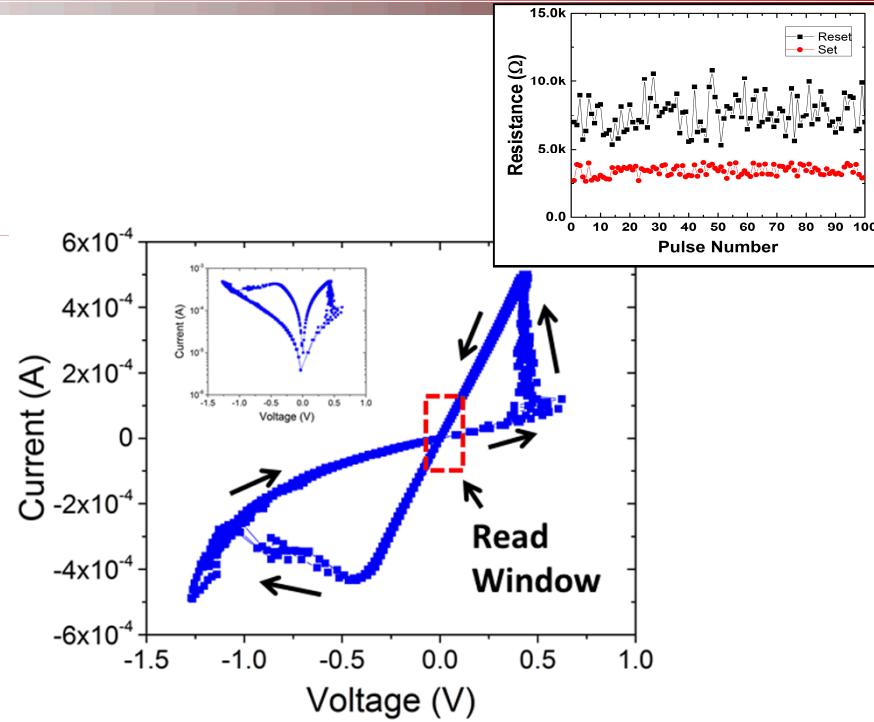
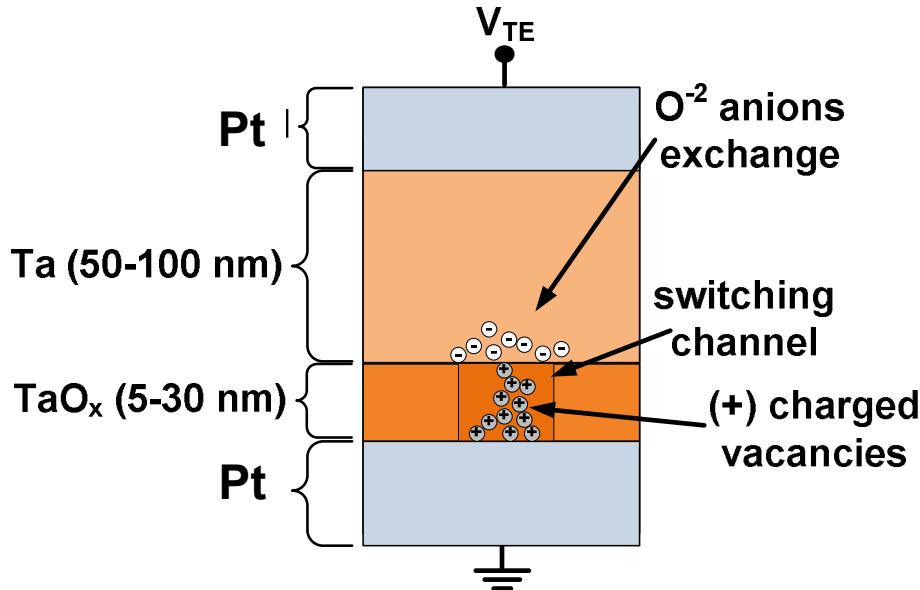
Test Device

Layer structure



Memristor I-V Characteristics

- Resistive RAM stores state in the form of resistance
- Applied current and voltage can change resistance state
 - Hysteresis loop
- Low voltages can read state
 - Read window

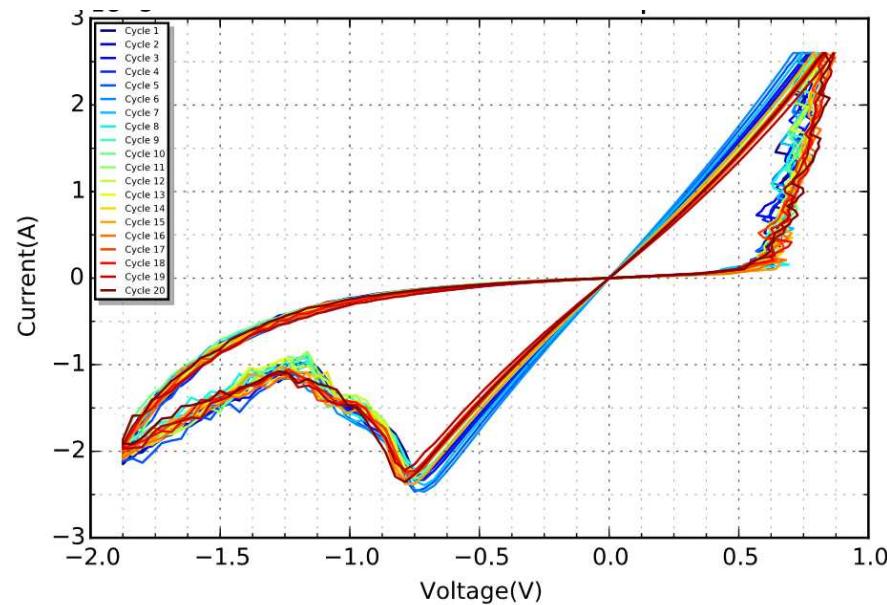


- Resistive switching
 - Oxygen vacancies
- TaO_x
 - Oxygen anions

IAD Improvements

High Repeatability

- More precise control over film thickness, stoichiometry and reduction in surface roughness
 - Improvements in yield and uniformity
 - Process adjustments easier due to higher repeatability



Ta₂O_x by IAD:

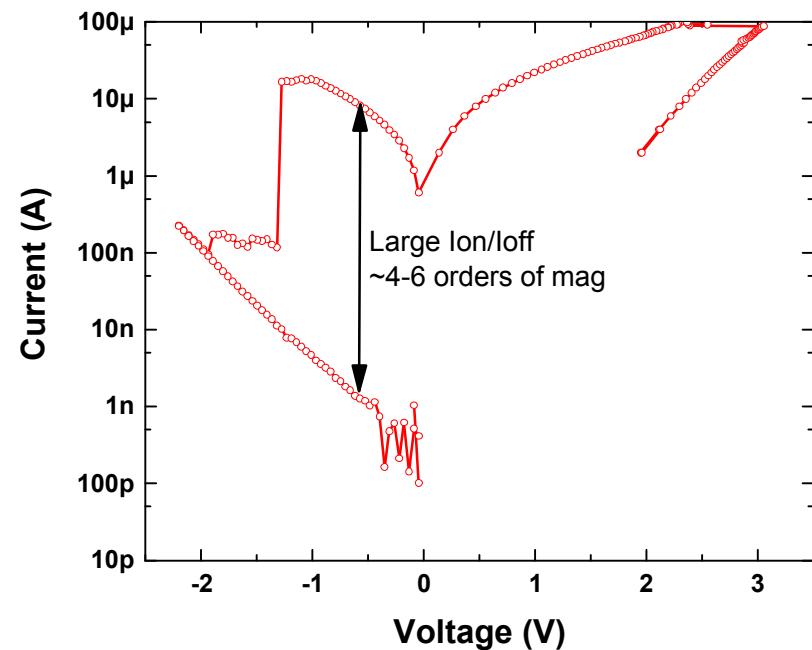
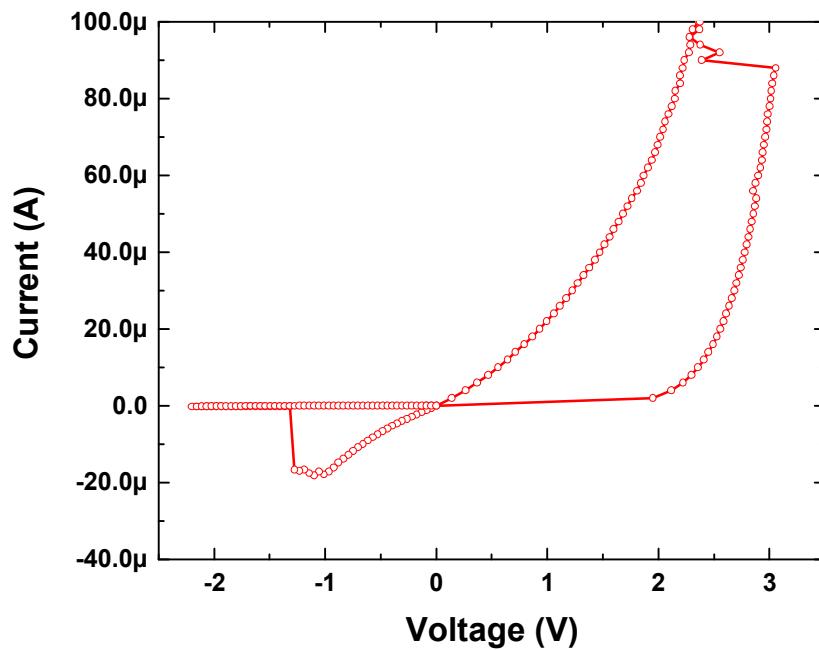
Device Results

High yield; some batches 100% working devices

High resistance operation

Very high R_{off}/R_{on} ratio; as high as 6 orders of magnitude – critical for analog applications

Highly nonlinear IV curve – may provide self-selection



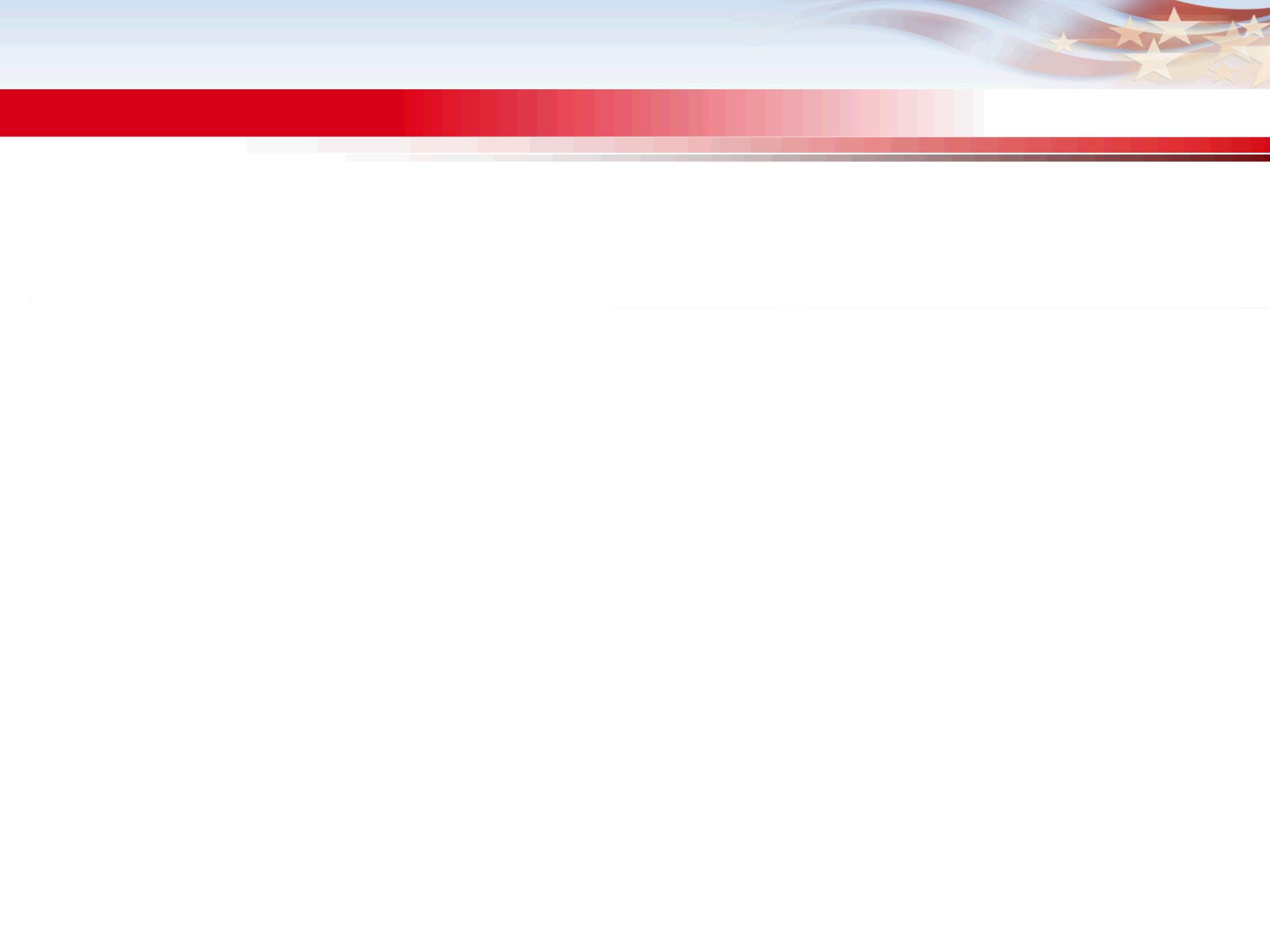
Conclusions

- Previous Metal Oxide ReRAM cells have relatively high cycle to cycle variability, which may significantly limit the resolution of an analog accelerator
- Ion Assisted Deposition of TaO_x shows promise for significantly reducing that variability and improving device performance.
- IAD demonstrated excellent control over stoichiometry

Acknowledgements:

This project is funded by Sandia's Laboratory Directed Research and Development (LDRD) Program.

Carl Smith for film deposition.



Neural Algorithm Computing

Next Generation

Problem: neural algorithm training requires significant memory and logic interaction

What is the most efficient way to combine memory, logic and interconnects?

SRAM: on chip cache memory is limited to ~40MB digital (Intel E7)
ns latency, max regardless of CPU, GPU or ASIC

Off chip communication to DRAM costs >100 pJ/op, ~10ns latency

Resistive memory on chip: can be stacked to >TB/cm², >100 layers

On chip access, <1pJ per op and <1ns latency possible

Terabit densities on single chip – on chip wiring is low energy!

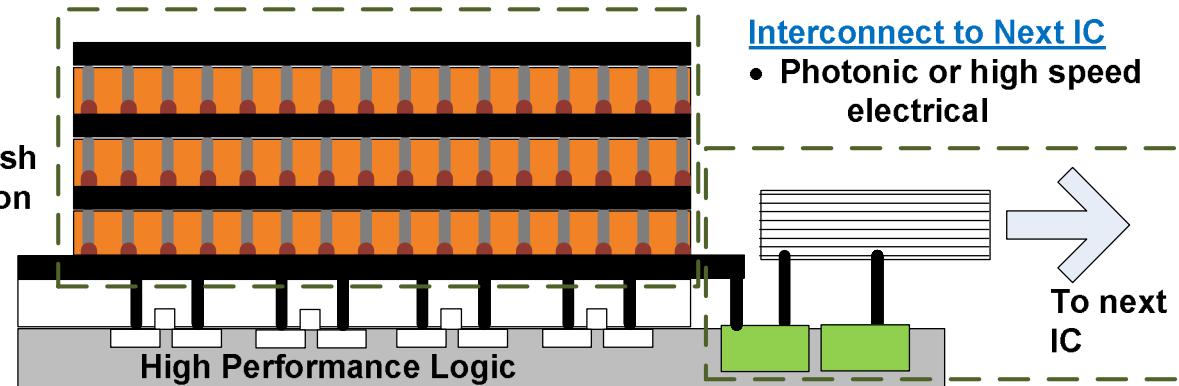
Sub 1V switching – minimal CV²f loss (DRAM 2-5V)

Significant power savings using a ReRAM based HW accelerator

Example: Taha found 16x reduction in power, 6x improvement in perf per chip over SRAM

ReRAM Layers:

- Terabit cm⁻² per layer
- Replaces DRAM & flash
- <1 pJ, <10 ns operation



Data Centers are Expanding Rapidly

Problems for analysis and energy consumption

